

ABSTRACT

In a sputtering target comprising at least indium oxide and zinc oxide, the atomic ratio represented by $\text{In}/(\text{In}+\text{Zn})$ is set to a value within the range of 0.75 to 0.97, a hexagonal layered compound represented by $\text{In}_2\text{O}_3(\text{ZnO})_m$ wherein m is an integer of 2 to 20 is contained, and the crystal grain size of the hexagonal layered compound is set to a value of 5 μm or less.



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